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PATENT ABSTRACTS OF JAPAN

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(21)Application number :	04-218703	(71)Applicant :	NIPPON TELEGR & TELEPH CORP <NTT>
(22)Date of filing :	27.07.1992	(72)Inventor :	TANAKA HARUYORI KAWAI YOSHIO MATSUDA KOREHITO

(54) POSITIVE RESIST MATERIAL

(57)Abstract:

PURPOSE: To provide a positive resist material for high energy beam exposure having high sensitivity and resolution and excellent in process adaptivity.

CONSTITUTION: In the high energy beam sensitive positive resist containing a resin (A) made by substituting t-butoxycarbonyloxy group for one part of hydroxide group of polyhydroxy styrene, a dissolution inhibitor (B) and an acid generating agent and capable of developing by an alkali aq. solution, (B) contains above one of t-butoxycarbonyloxy group in one molecule, (C) is made by mixing above two kind of the acid generating agent expressed by a formula (chem.1), (R)nAM (in the formula, R is the same or different and is aromatic group or substituted aromatic group, A is sulfonium or iodonium. M is tosylate group or triflate group and (n) is 2 or 3), and the weight ratio is $0.07 \leq B \leq 0.40$, $0.005 \leq C \leq 0.15$, $0.55 \leq A$ and $A+B+C=1$.

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